U.S. Patent and Trademark Office: U. PARTMENT OF COMMERCE Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number

Application Number

TRANSMITTAL

KW IBAULA

09/418,818

FORM (to be used for all correspondence after initial filling)			Filing Date		October 15, 1999
			First Named Inventor		Cheung, David
			Art Unit		1763
			Examiner Name		Rudy Zervigon
Total Number of Page		Attorn	ey Docket Number	1084D01T9320	
ENCLOSURES (Check all that apply)					
Fee Transmittal Form		Drawing(s)		,	After Allowance Communication to Group
Fee Attached		Licensing-related Papers		ed Papers	Appeal Communication to Board of Appeals and Interferences
Amendment / Reply		Petition		•	Appeal Communication to Group (Appeal Notice, Brief, Reply Brief)
☐ After Final		Petition to Convert to a Provisional Application			Proprietary Information
Affidavits/declaration(s)		Power of Attorney, Revocation Change of Correspondence Address			Status Letter
Extension of Time Request		Terminal Disclaimer			Other Enclosure(s) (please identify below):
Express Abandonment Request		Request for Refund CD, Number of CD(s)			Two Return Postcards
☐ Information Disclosure Statement				(-,	
Certified Copy of Priority Document(s)		Remarks The Commissioner is authorized to charge any additional fees to Deposit Account 20-1430.			
Response to Missing Parts/ Incomplete Application					APR 2 3 2003
Response to Missing Parts under 37 CFR 1.52 or 1.53					GROUP 1700
SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT Firm Townsend and Townsend and Crew LLP					
or Individual	Chun-Pok Leung Reg. No. 41,				. 41,405
Signature	4-14-0)				
Date 4 - 14-0)					
CERTIFICATE OF TRANSMISSION/MAILING					
Thereby certify that this correspondence is being facsimile transmitted to the USPTO or deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231 on this date: April 11, 2003					
Typed or printed Andrea S. Beck			•		1
Signature					Date 4/14/07

This collection of information is required by 37 CFR 1.5. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 12 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, Washington, DC 20231.

PA 3298055 v1

APR 22 MM DES

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to:

Attorney Docket No.: 1084D01T9320

TTC Ref. No.: 016301-009320

Assistant Commissioner for Patents Washington, D.C. 20231

on dail A doos

TOWNSEND and TOWNSEND and CREW LLP

By And

#2**0**F

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

David Cheung et al.

Application No.: 09/418,818

Filed: October 15, 1999

For: METHOD AND APPARATUS FOR

DEPOSITING ANTIREFLECTIVE

COATING

Examiner:

Rudy Zervigon

Art Unit:

1763

AMENDMENT

RECEIVED

APR 2 3 7003

Assistant Commissioner for Patents Washington, D.C. 20231

GROUP 1700

Sir:

In response to the Office Action mailed January 14, 2003, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 7 and 8 without prejudice; and amend claims 1, 44, 49, 53, 54, 55, 57, and 62 as follows. The remaining claims are unamended, but are reproduced below for the Examiner's convenience and reference.

- 1. (Amended) A substrate processing system, comprising:
- a vacuum chamber;
- a substrate supporter, located within the vacuum chamber, for holding a

substrate;